	Application No.	Applicant(s)	
Notice of Allowability	09/905,027	CRAIGHEAD ET AL.	
	Examiner	Art Unit	
	Michael Trinh	2822	pw
The MAILING DATE of this communication appearable All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apply or other appropriate communication IGHTS. This application is subject to	plication. If not include will be mailed in due o	ed course. THIS
1. \boxtimes This communication is responsive to <u>Amendment filed 11/1</u>	<u>28/03</u> .		
2. The allowed claim(s) is/are <u>1-7,9-18,20-24,48 and 49</u> .			
3. The drawings filed on 13 July 2001 are accepted by the Ex	xaminer.		
 4. Acknowledgment is made of a claim for foreign priority ur a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	e been received. e been received in Application No		ion from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the req	uirements
5. A SUBSTITUTE OATH OR DECLARATION must be subminformal PATENT APPLICATION (PTO-152) which give			OTICE OF
6. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) I including changes required by the Notice of Draftspers	son's Patent Drawing Review (PTO-	948) attached	
1) 🗌 hereto or 2) 📗 to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the C	office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			back) of
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT			ote the
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/O Paper No./Mail Date	5. ☐ Notice of Informal P 6. ☐ Interview Summary Paper No./Mail Dat 7. ☑ Examiner's Amendn 8. ☑ Examiner's Stateme 9. ☐ Other	(PTO-413), le nent/Comment	
		Michael Trinh Primary Examiner	/)

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DETAILED ACTION

*** This office action is in response to Applicant's Amendment filed on November 28, 2003. Claims 1-7, 9-18,20-24, and 48-49 are currently pending. Claims were canceled.

Examiner's Amendment

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

<u>IN THE SPECIFICATION:</u> (correct of the year as it is consistent with PTO records)

** Specification page 1, line 4, under the section of "CROSS REFERENCE TO RELATED APPLICATIONS",

after "60/115,854, filed" change "January 13, 1998" to -- January 13, 1999--.

Allowable Subject Matter

- 2. Claims 1-7, 9-18,20-24, and 48-49 are allowed.
- 3. The following is a statement of reasons for the indication of allowable subject matter:

Applicant's amendment and convincing remarks of record have overcome the rejections. The references of record, alone or in combination, do not fairly anticipatively disclose each and every aspect of the claimed method, or fairly make a prima facie obvious case of the claimed method, a) in combination with other processing claimed limitations as recited in base claims 1 and 9, the inclusion of depositing a ceiling layer to cover a sacrificial layer, patterning and etching the ceiling laver to form a ridge waveguide intersecting the location of a desired fluid working gap, patterning and etching the ceiling layer to define at least one access hole leading to said sacrificial layer, and removing the sacrificial layer to produce a working gap; b) and in combination with other processing claimed limitations as recited in base claim 23, the inclusion of patterning and etching a substrate to produce a surface having a vertical sidewall intersecting the substrate at the base of the sidewall; depositing a thin film conformal sacrificial layer on the

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substrate and covering the sidewall, removing by an unmasked RIE the thin film sacrificial layer on the sidewall and on the substrate, while leaving said sacrificial wire along said base; depositing a ceiling layer on said substrate and said sidewall and covering said wire; and removing said sacrificial wire to produce a nanochannel between said substrate, sidewall, and ceiling layer; or c) an in combination with other processing claimed limitations as recited in base claim 24, the inclusion of oxidizing the patterned sacrificial silicon layer to reduce the width and height of the sacrificial wire bay consuming silicon from the surface of the wire to form a silicon oxide coating, and removing the sacrificial wire from within said silicon oxide coating to produce a nanochannel.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael M. Trinh whose telephone number is (571) 272-1847. The examiner can normally be reached on M-F: 8:30 Am to 5:00 Pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on (571) 272-1852. The fax phone numbers for the organization where this application proceeding is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

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